

Front-end Electronics for DEPFET Pixel Detectors at SuperBelle

Hans Krüger, University of Bonn
for the DEPFET Collaboration

The DEPFET Collaboration

- University of Barcelona^(*)
- University Ramon Lull, Barcelona
- University of Bonn^(*)
- University of Heidelberg^(*)
- University of Giessen
- University of Göttingen
- University of Karlsruhe
- IFJ PAN, Krakow
- MPI Munich
- Charles University, Prag
- University of Santiago de Compostela
- IFIC Valencia

Collaboration started with μ VTX R&D for ILC – now in good position for PXD development for Belle 2

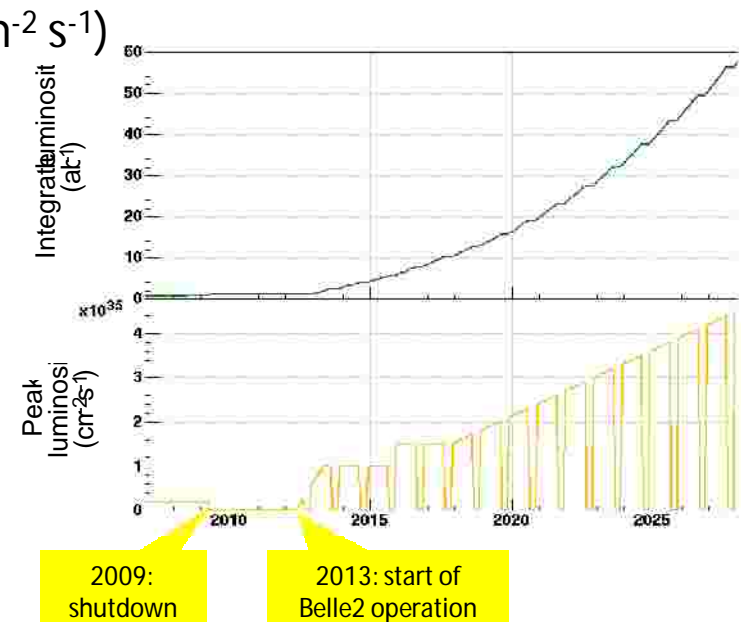
^(*) ASIC design activity

- Upgrade of the Belle detector at KEKB – Belle 2 (aka SuperBelle)
- Detector concept
- Front-end electronics
- Prototype results

Upgrade of the KEK B factory

- Asymmetric e^+/e^- collider (3.5 GeV, 8 GeV)
 - 900 million B meson pairs (since 1999)
 - study CP violation via $B^0/B^0\text{-bar}$ decays
 - rare decay modes \Rightarrow need even more statistics
- Machine upgrade: Super KEK B
 - increase luminosity ($1.7 \times 10^{34} \text{ e}^-$ up to $8 \times 10^{35} \text{ cm}^{-2} \text{ s}^{-1}$)
 - high beam current (9.4/4.1A) or
 - nano beam
 - crab crossing
 - ...

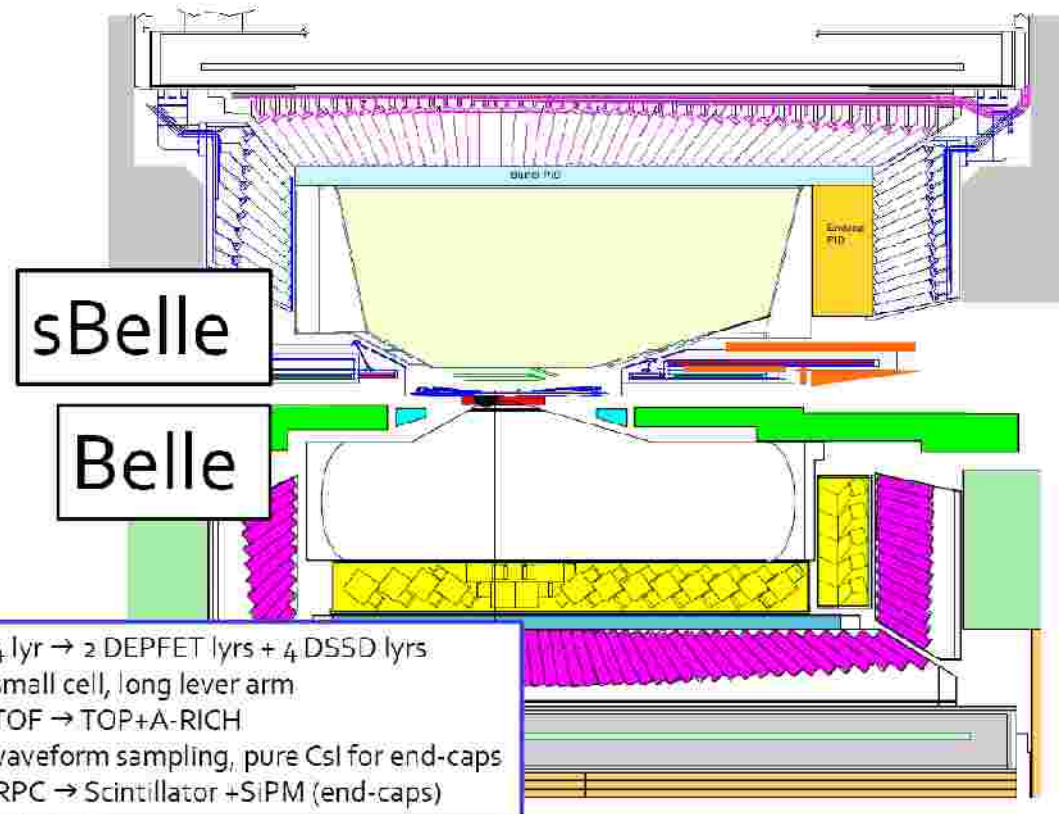
Belle detector



Belle Detector Upgrade – SuperBelle

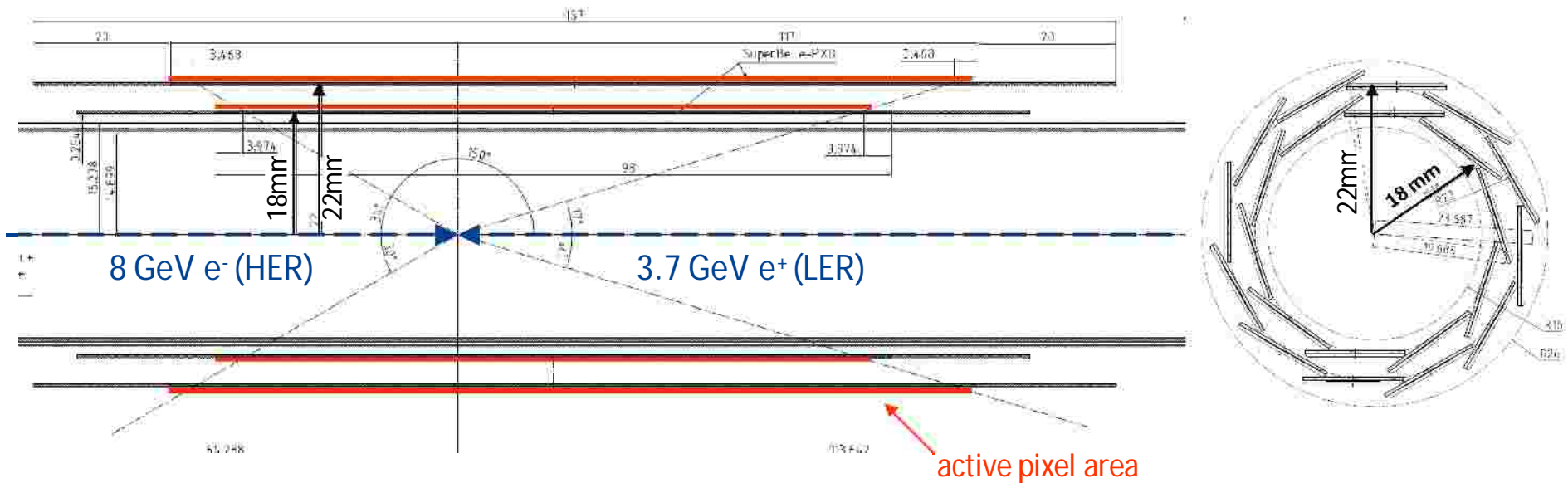
- various upgrades for all sub detectors
 - background reduction
 - vertex resolution
 - rate capability
 - particle identification

- silicon vertex detector upgrade
4 layer DSSD à 2 layer pixels + 4 DSSD



- challenges for the detector
 - higher background (x20) à radiation damage, occupancy
 - higher event rate (x50) à higher trigger rate, DAQ, computing

DEPFET Pixel Vertex Detector – PXD



- Two layer vertex detector
 - layer 1: 10 modules at 1.8 cm radius
 - layer 2: 12 modules at 2.2 cm radius
 - optional layer 0 at 1.3 cm radius with beam pipe upgrade
 - 17° - 150° acceptance ($\eta = [0.55 .. 0.3]$)

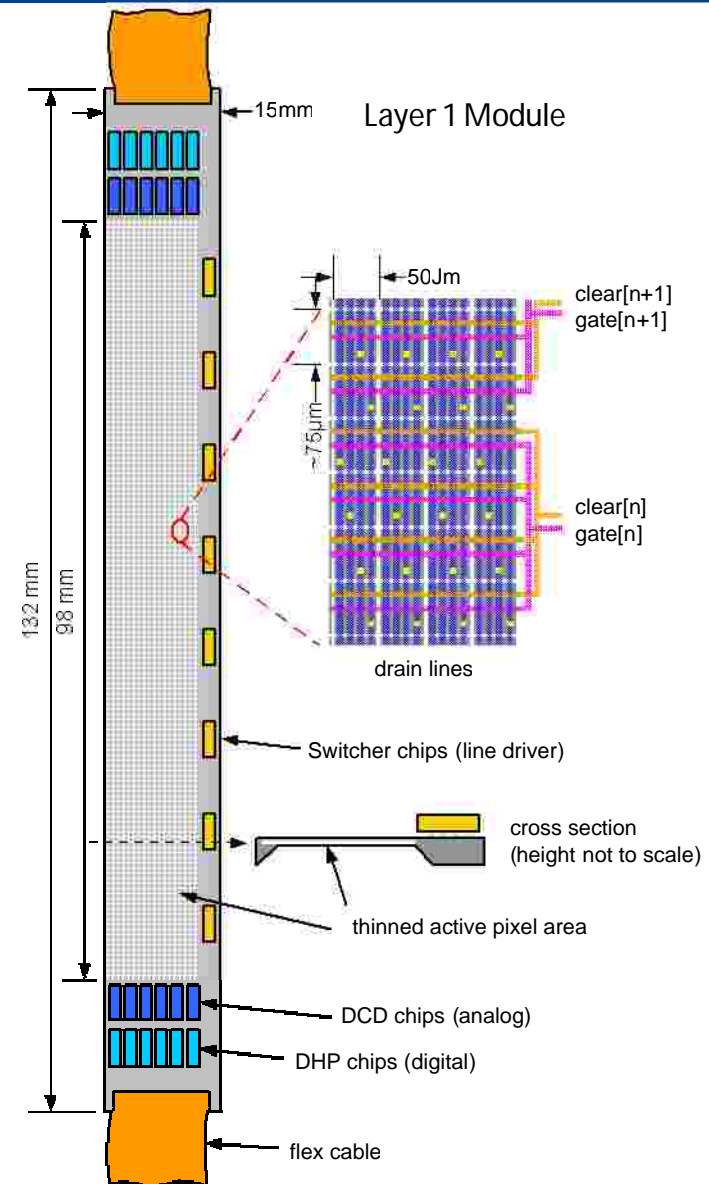
Some more Specifications...

- occupancy: ~ 0.2 hits/ $\mu\text{m}^2/\text{sec}$ (estimated for $1 \times 10^{35} \text{ cm}^{-2}\text{sec}^{-1}$, @ 1.8cm radius)
- spatial resolution : $< 10 \mu\text{m}$ (r-phi) (can be less in z)
- pixel size: $50 \mu\text{m}$ (r-phi) x $\sim 60 \mu\text{m}$ (z-axis)
- material budget $< 0.15 \% X_0$ per layer
- read-out time: $10 \mu\text{s}$ ($20 \mu\text{s}$)
- sample (row) rate: 12 MHz
- layer1 half-module active area: 4.9 cm x 1.2 cm
- #pixels: 240 x 500 (800)
- anticipated radiation: ~ 1 Mrad per year of operation

“All-silicon” DEPFET Module

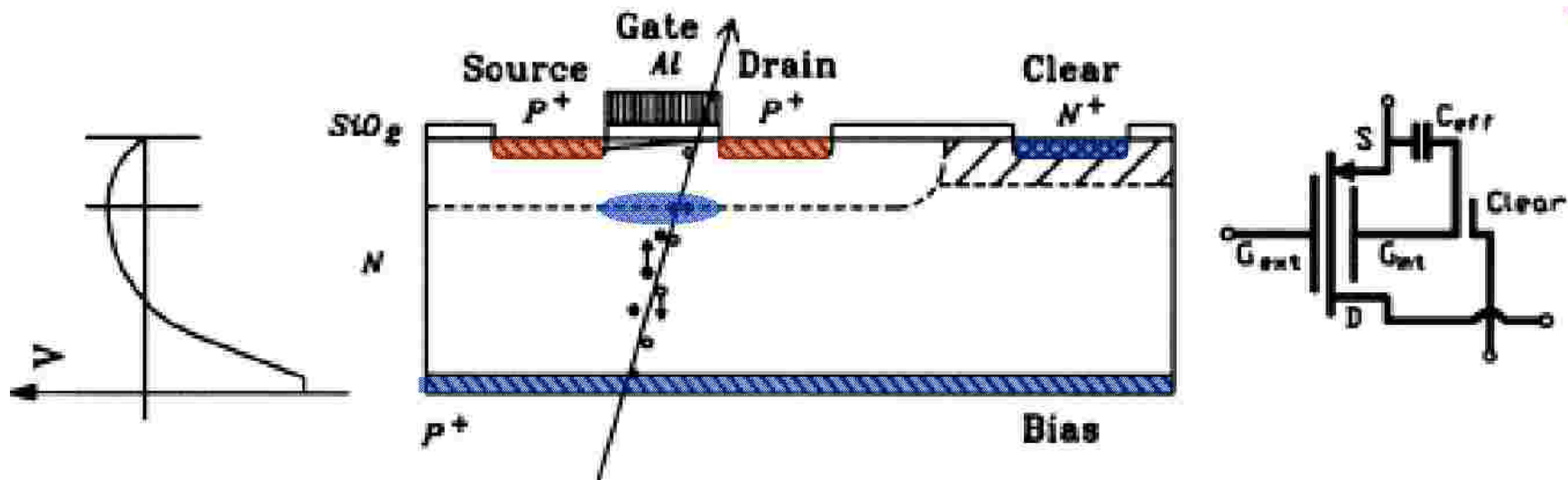
- active pixel area thinned to $50\ \mu\text{m}$
 - low mass design
- surrounding (non-thinned) frame
 - mechanical support
 - mounting and routing for the ASICs
- ASICs bump bonded directly to the DEPFET substrate
- Independent read-out from both sides (half modules)

see talk by Carlos Lacasta on Friday afternoon for more details on the DEPFET sensor design & performance



The DEPFET Principle

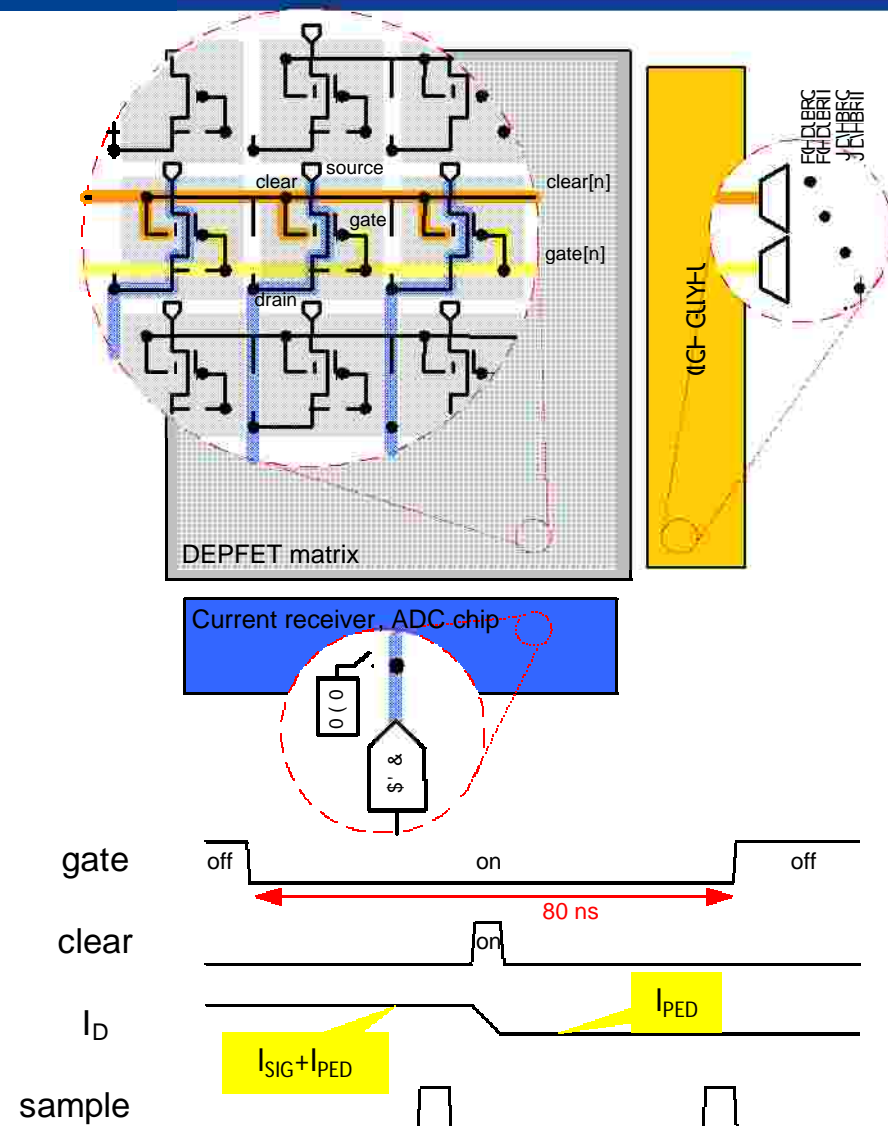
- p-FET (MOSFET) integrated in the sensor substrate
- fully depleted bulk (sideward depletion)
- internal gate (deep n implantation) collects signal electrons \rightarrow low C_D , low noise
- charge collection during external gate being switched off \rightarrow low power
- integrating device, discharge internal gate with positive pulse applied to the clear contact



J. Kemmer and G. Lutz Nucl. Instr. and Meth. A 253 (1987), p. 365

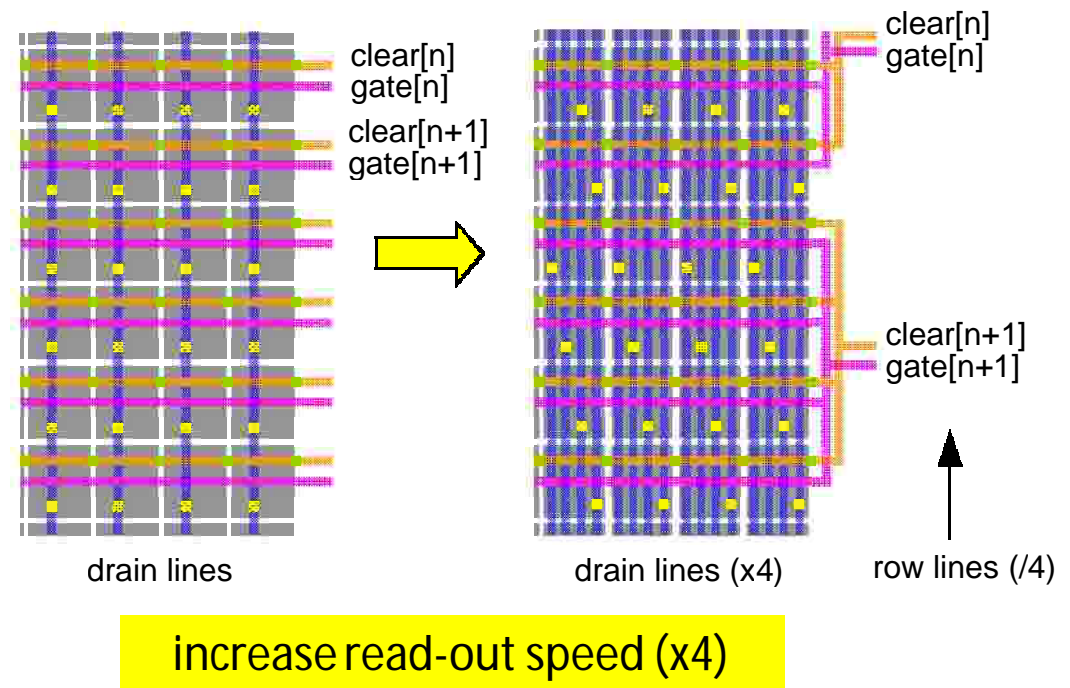
DEPFET Matrix Read-out

- 'correlated double sampling'
 1. one row selected at a time
 2. sample drain current ($I_{ped} + I_{sig}$)
 3. clear internal gates of selected row
 4. sample drain current (I_{ped}) again and subtract from stored current $\rightarrow I_{sig}$
 5. digitize I_{sig}
- clear requirements (complete clear)
 - > 10V swing
 - > 15 ns pulse width
- read-out speed
 - drain (current) read-out \rightarrow low voltage swing
 - low input resistance of the r/o chip

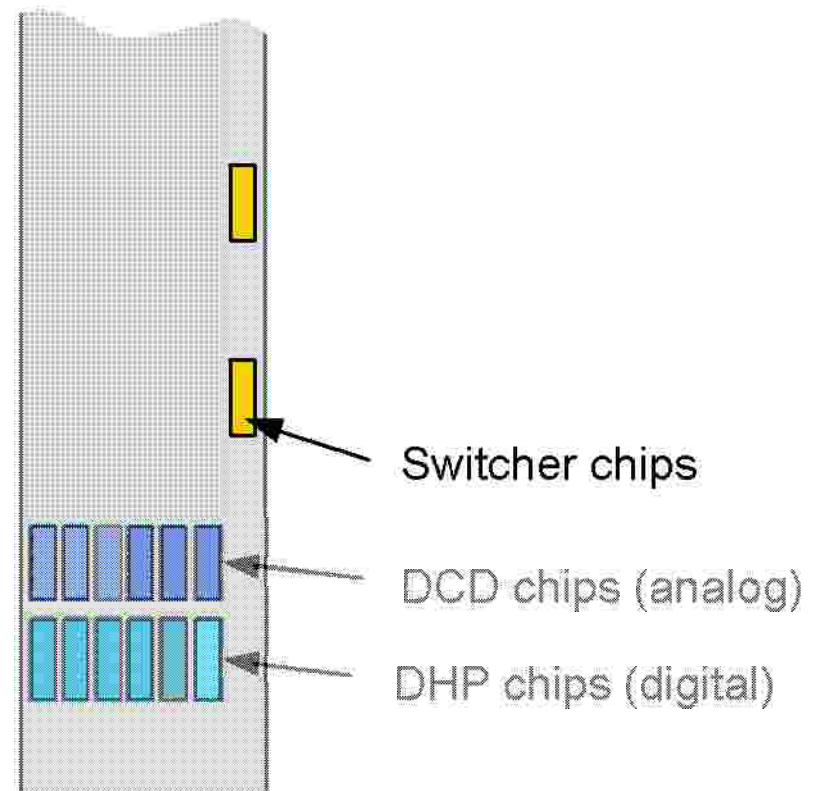


DEPFET Matrix Layout

- 4-fold parallel column read-out
 - increase r/o speed by x4
 - reduced number of line driver channels (rows)
 - less material in the acceptance region
 - $50\ \mu\text{m}$ pixel width \Rightarrow $12.5\ \mu\text{m}$ drain line pitch (technology limit)
 - need to flip chip the read-out chip

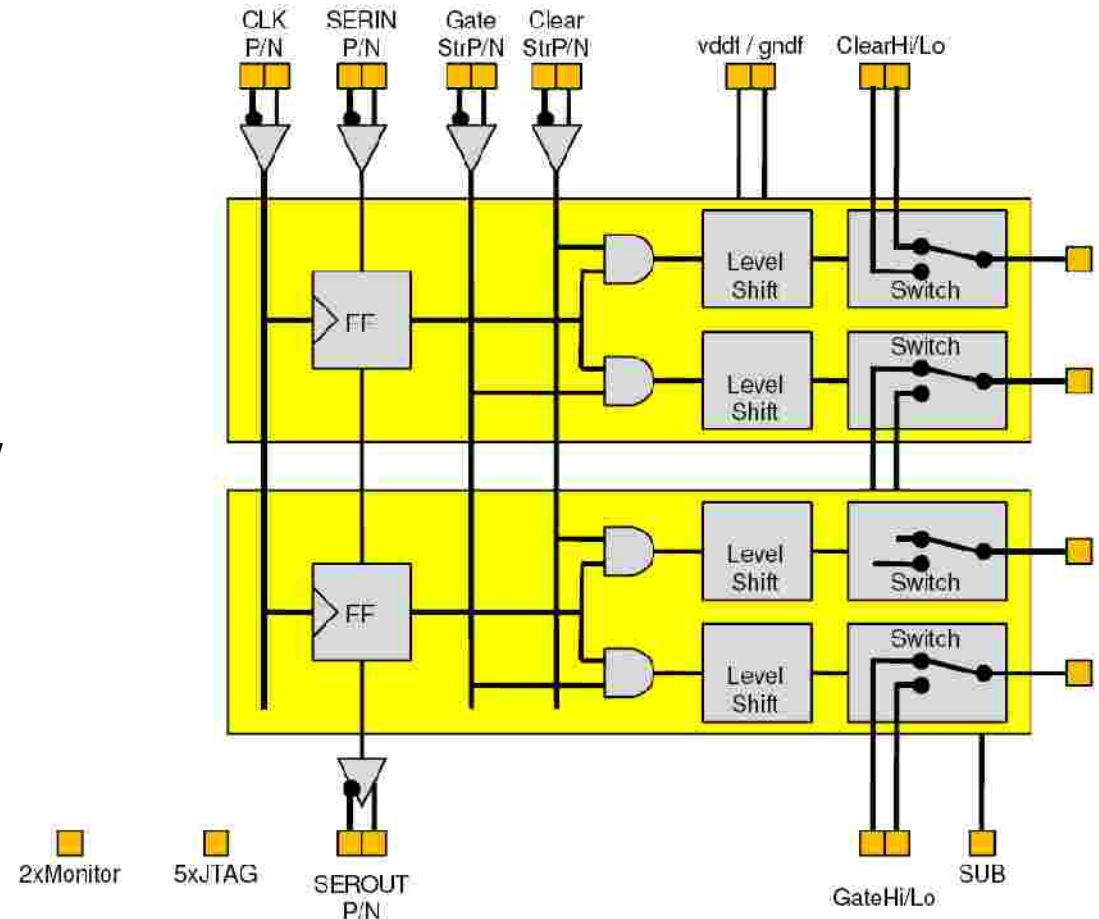


Switcher Chip (Line Driver)



Switcher Chip Block Diagram

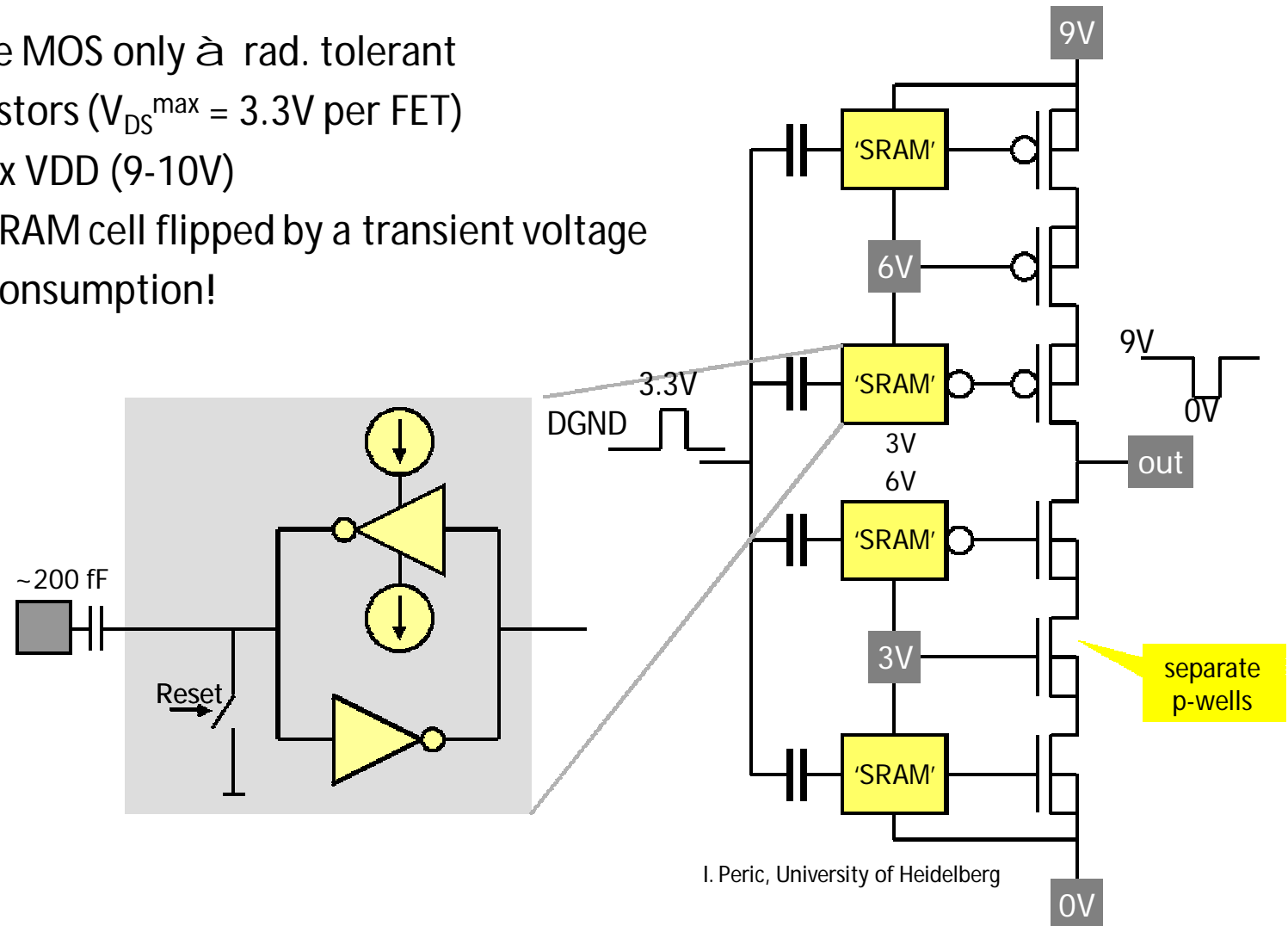
- high voltage (10-20V) pulses for clear and gate lines
- low output resistance (speed)
- radiation hard
- low power
(chip inside acceptance volume)
- Switcher chip developments (ILC, X-ray astronomy):
 - Switcher 2: 64 ch., analog I.s., $dU = 25\text{ V}$
 - Switcher 3: 128 ch., cap. I.s., $dU = 10\text{ V}$
 - Switcher 4: 64 ch., analog I.s., $dU > 30\text{ V}$
 - Switcher 5 (sBelle): tbd.



I. Peric et al, University of Heidelberg

Switcher 3 – Concept

- thin gate oxide MOS only à rad. tolerant
- stacked transistors ($V_{DS}^{max} = 3.3V$ per FET)
- max $dU_{out} = 3 \times VDD$ (9-10V)
- level shifter: SRAM cell flipped by a transient voltage
- no dc power consumption!



Switcher 3 – Implementation

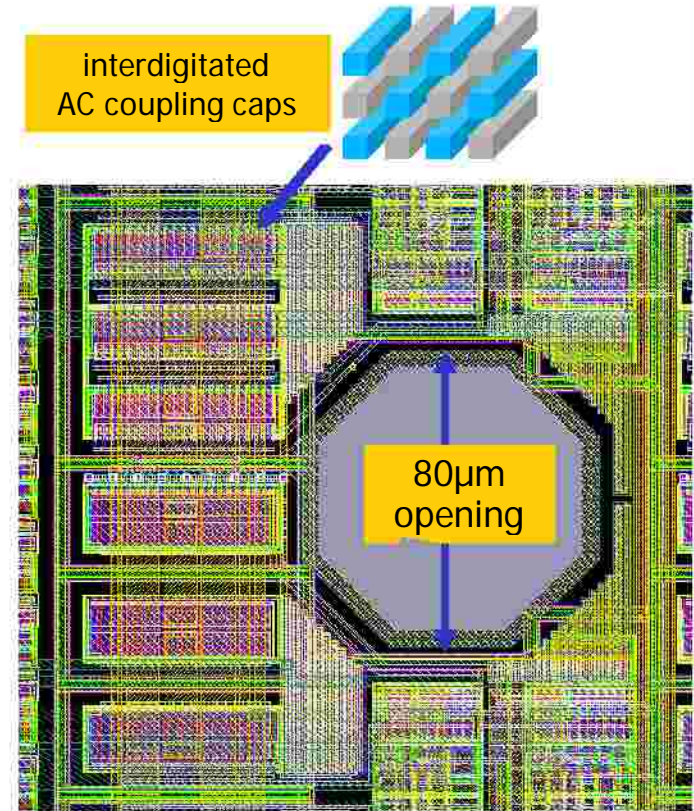
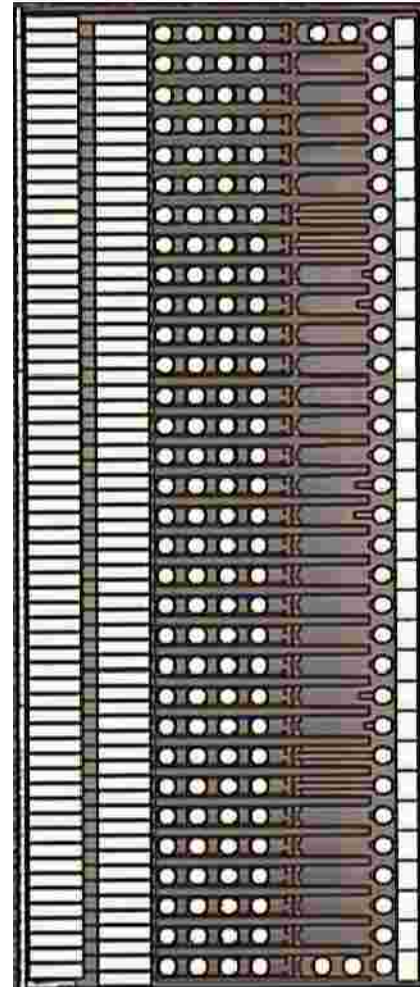
- Radiation tolerant layout in 0.35 μm twin-well technology
- 128 channels
- programmable sequencer

pro:

- very fast
- no DC power consumption

con:

- operation limited to 11.5 V
- need separate chips for clear and gate
- SEU in SRAM level-shifters can cause shorts



HV channel with 3+3 Switch transistors and 4 AC coupling stages (180x180 μm , M4 not shown)

I. Peric, University of Heidelberg

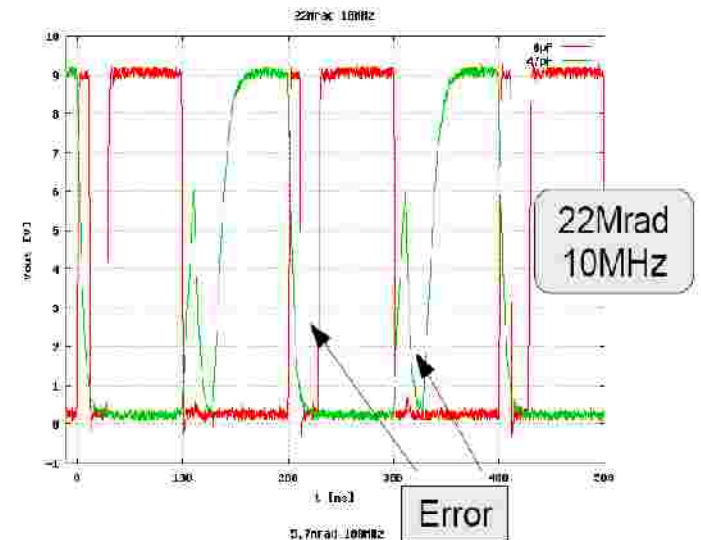
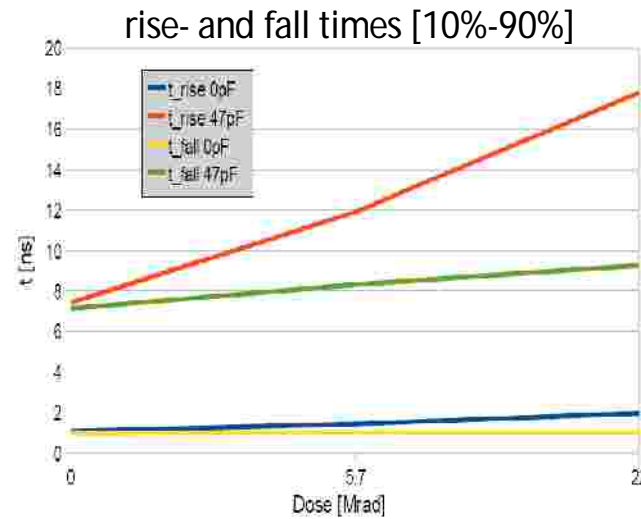
Switcher 3 – Measurements

up to 5.7 Mrad:

- chip running with 50 MHz clock
- increased rise/fall times

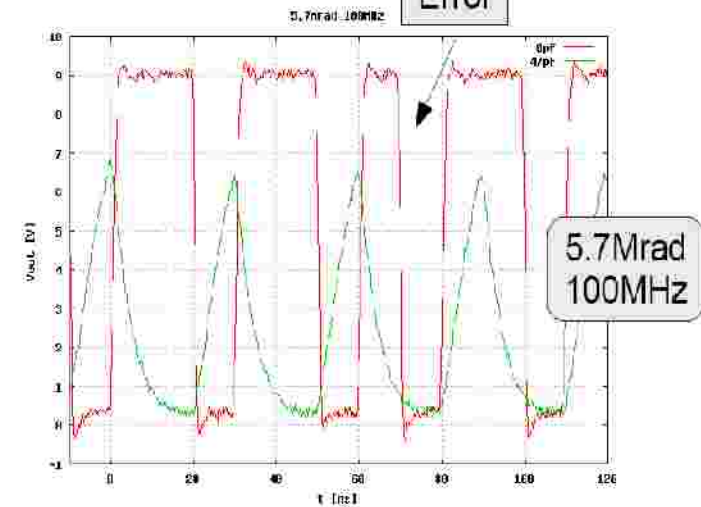
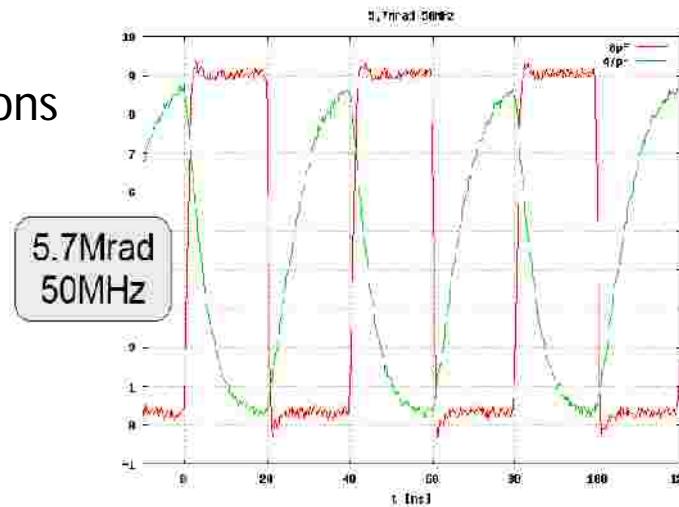
after 22 Mrad:

- digital errors
- even with lower (10 MHz) clock



reminder: Belle 2 conditions

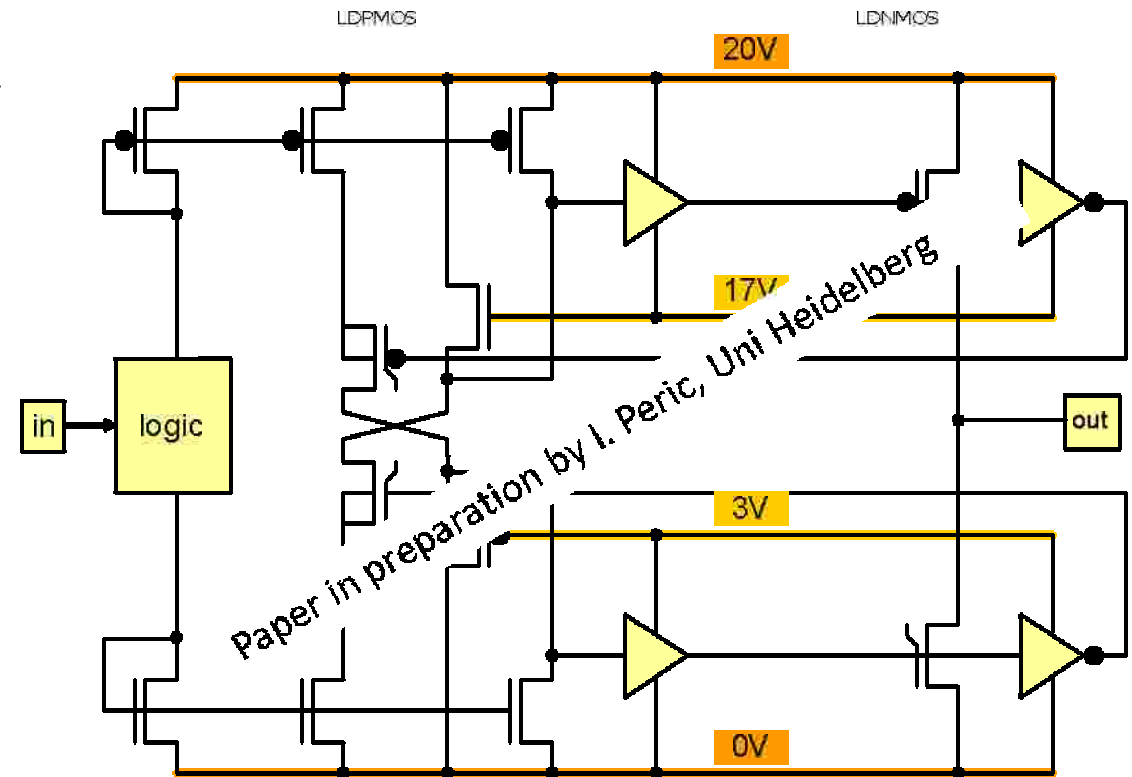
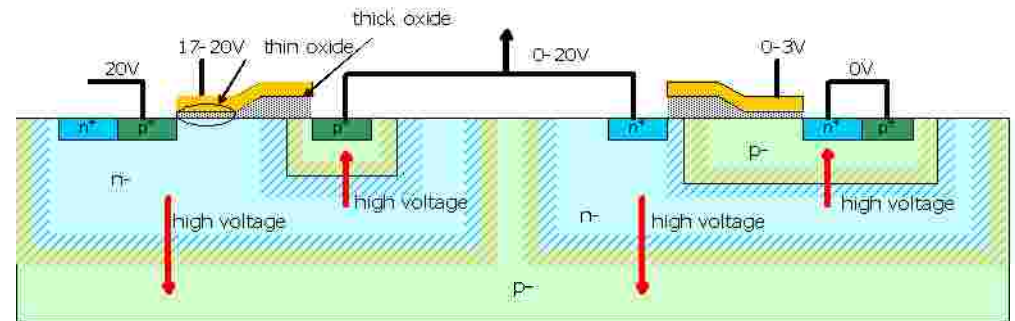
- ~1Mrad/yr
- 12 MHz clock



C. Kreidl, University of Heidelberg

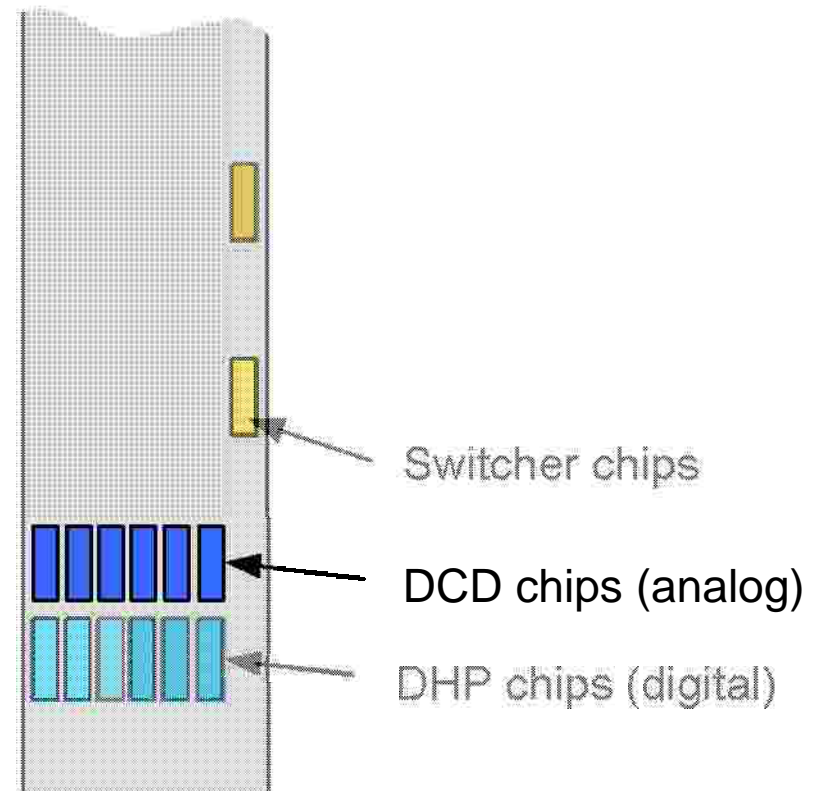
Switcher 4 – Concept

- new concept to achieve higher voltage swings
- 0.35 HV technology
 - rad. tolerant thin gate oxide MOS
 - lateral diffusion MOSFETs (LDMOS) for high voltage
 - rad. tolerant, enclosed design of NMOS HV transistors
- block diagram
 - drive N- and P-MOS output switches from separate rails (3V & 17V, generated on-chip)
 - ‘break before make’ switching



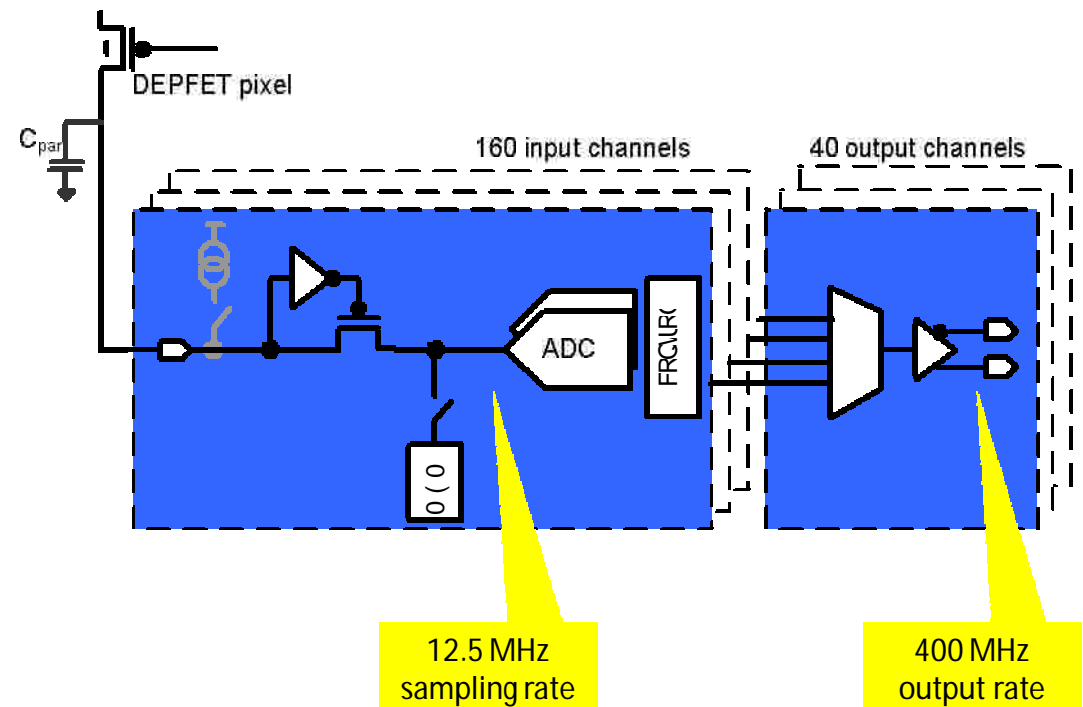
I. Peric, University of Heidelberg

Drain Current Digitizer – DCD



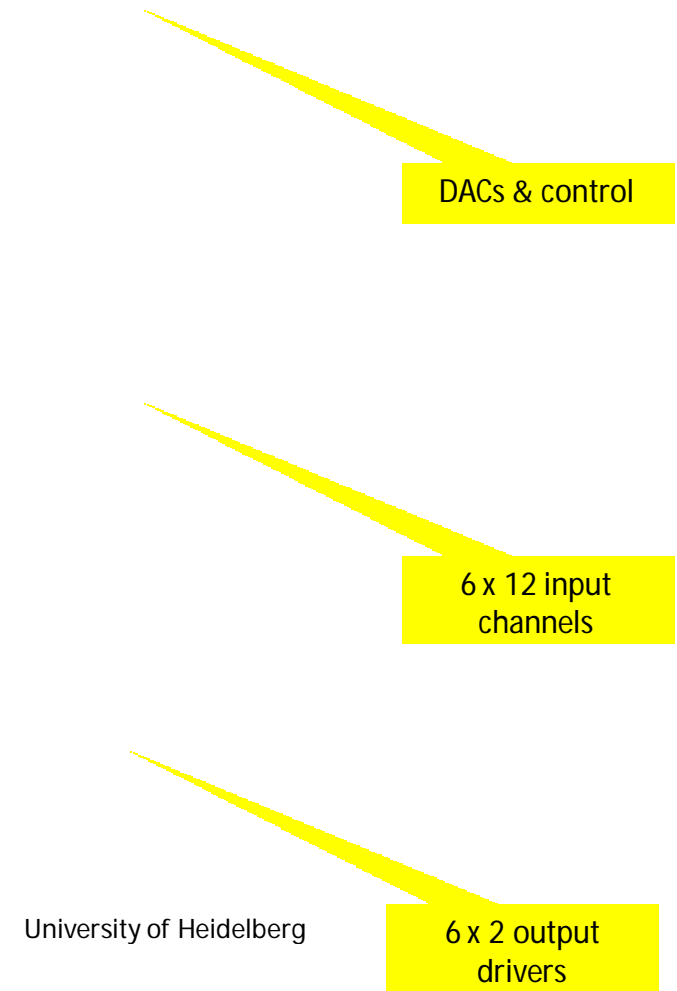
Drain Current Digitizer – DCD Chip

- receive drain current signals from the DEPFET matrix
 - need low r_{in} for fast settling time ($C_{PAR} \sim 50$ pF)
 - regulated cascode
- sample and subtract pedestal currents
 - current memory cells
- digitize signals
 - algorithmic ADC, 8 bit, 160 ns
 - two ADCs per channel @ 80 ns
 - serial output
- 4:1 multiplex ADC outputs (6:1) in current test chip



Drain Current Digitizer – DCD

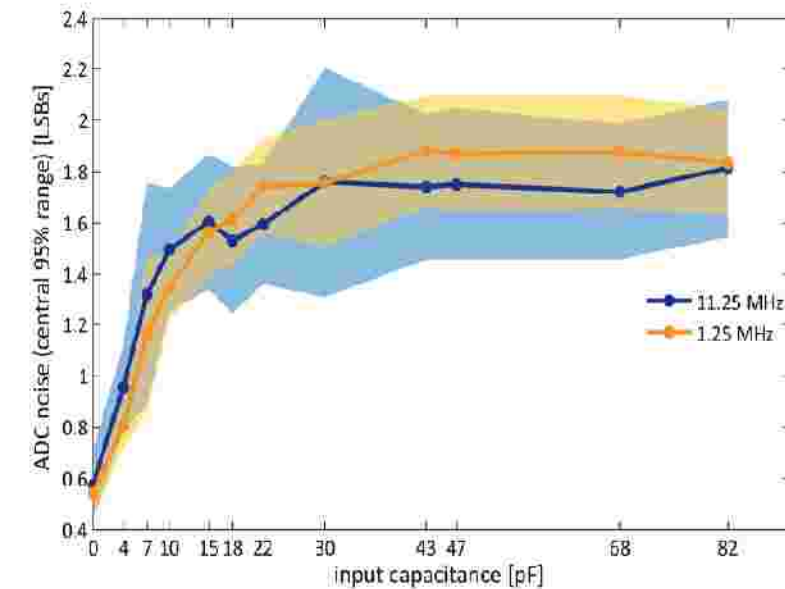
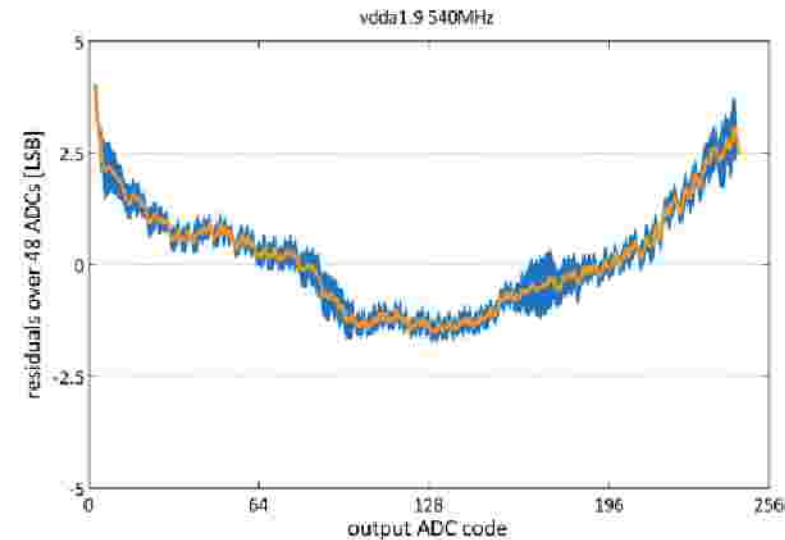
- DCD2: 72 ch. test chip
- 0.18 μm technology
- regulated cascode
- current memory cells
- two 8-bit algorithmic ADCs
- different test channels with parameter variations
- 6:1 multiplexed LVDS outputs
- bump bond IOs + wire bonds for testing



University of Heidelberg

DCD2 – Measurements

- linearity (@ 12.5 MHz sample rate)
 - max INL: 4 LSB
 - max DNL: 1 LSB
- noise (including reg. cascode)
 - 0.6 – 1 LSB (w/o cap. input load)
 - < 2 LSB with up to 82 pF load



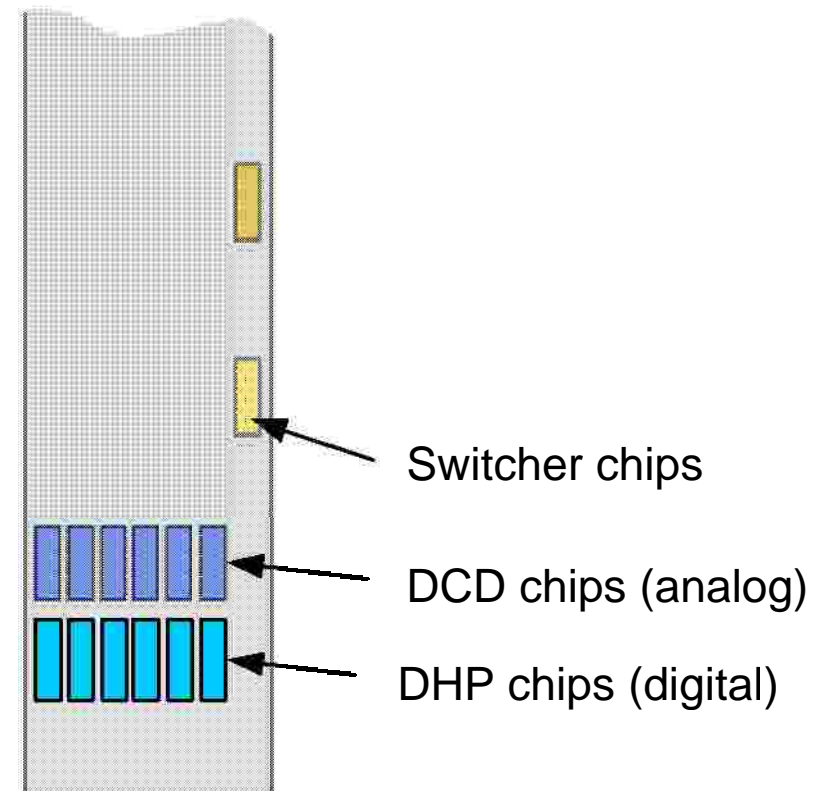
DCD2 – Measurements (contd.)

- input range: [0..24 μ A] ($I_{\text{SIG_MIP}} \sim 12 \mu\text{A} @ 450 \mu\text{m}$, $1.3 \mu\text{A} @ 50 \mu\text{m}$)
- LSB: 100 nA (higher than designed $\hat{=}$ increased bias for 500 MHz operation)
- gain: $10 \pm 0.1 \text{ LSB} / \mu\text{A}$
- noise: $< 2 \text{ LSB} @ 60 \text{ pF}$ input capacitance
- power consumption: 6 mW/channel

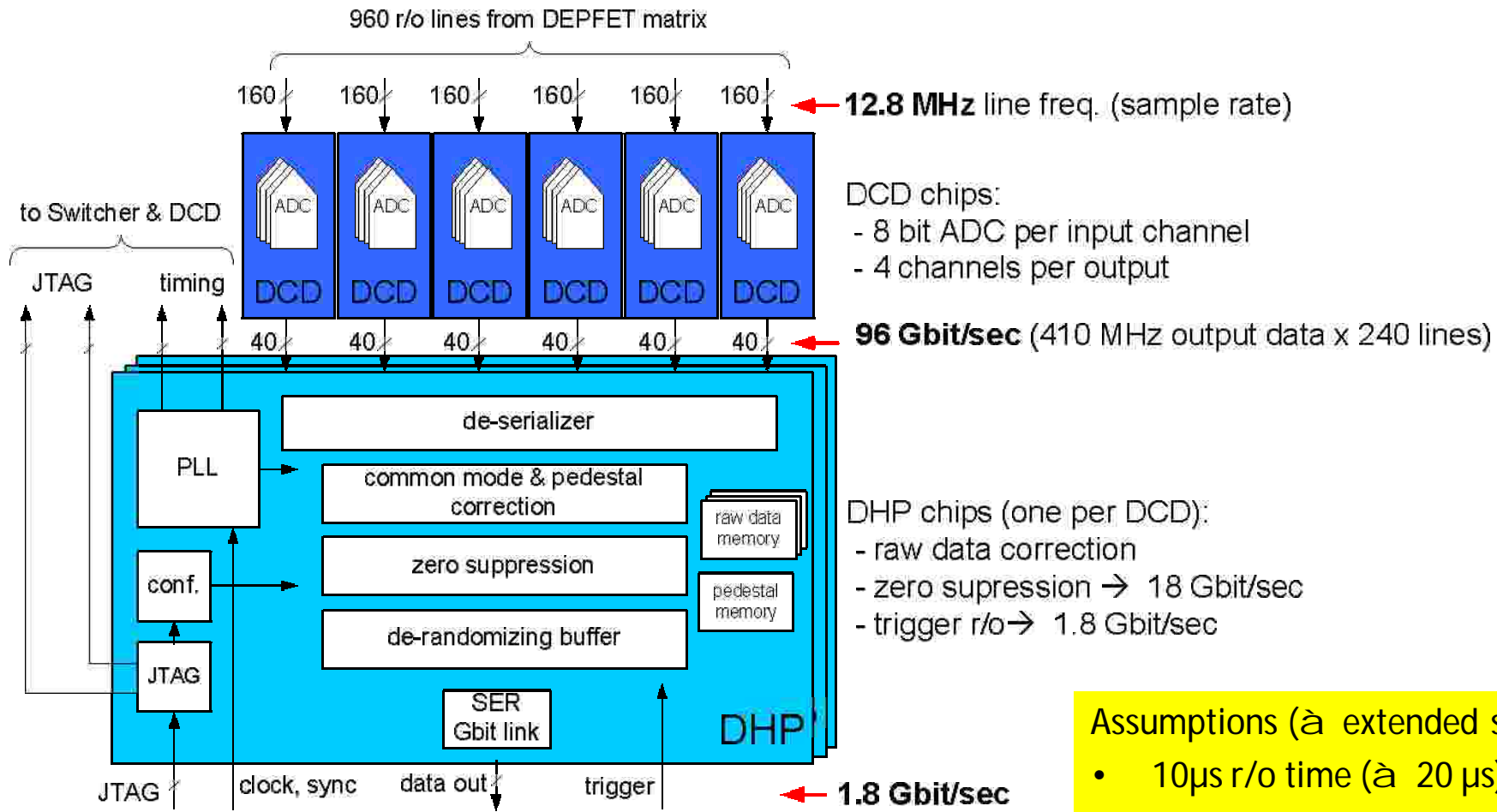
- DCD fully operational @ 600 MHz clock speed (12.5 MHz sampling frequency)
- adjust input range to dynamic signal range from thin detectors

- to do: dynamic tests (settling time, bandwidth ...), radiation tests

Data Handling Processor – DHP



DHP – Signal Rates & Data Flow

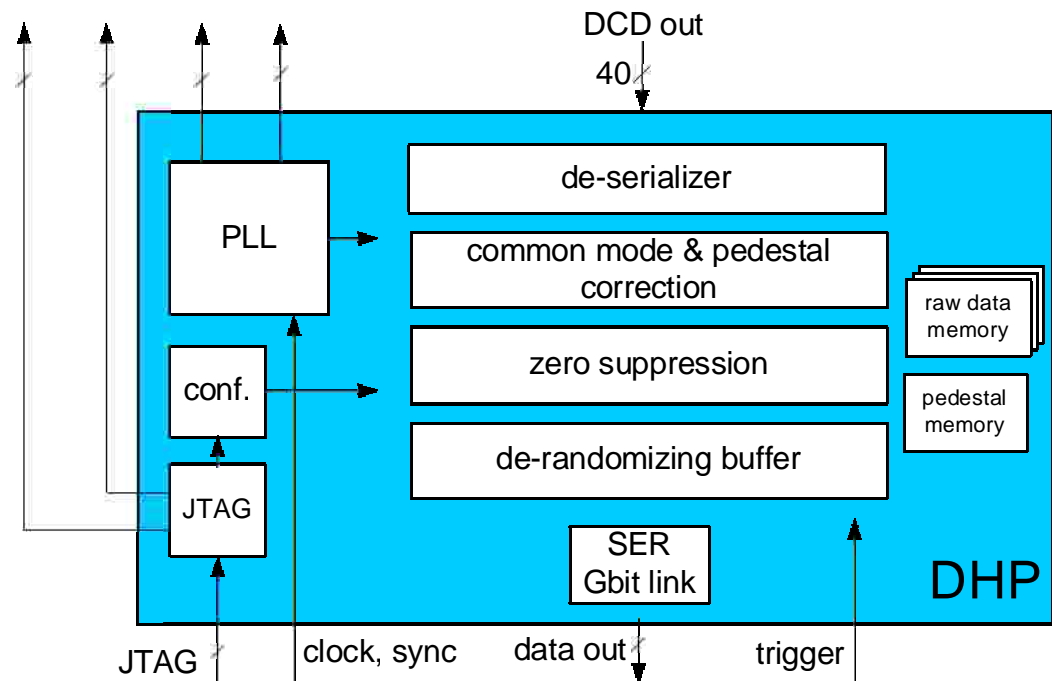


Assumptions (à extended specs.)

- 10 μ s r/o time (à 20 μ s)
- 128 switcher channels (à 256)
- 10 kHz trigger (à 30 kHz or more)
- 3-4% occupancy

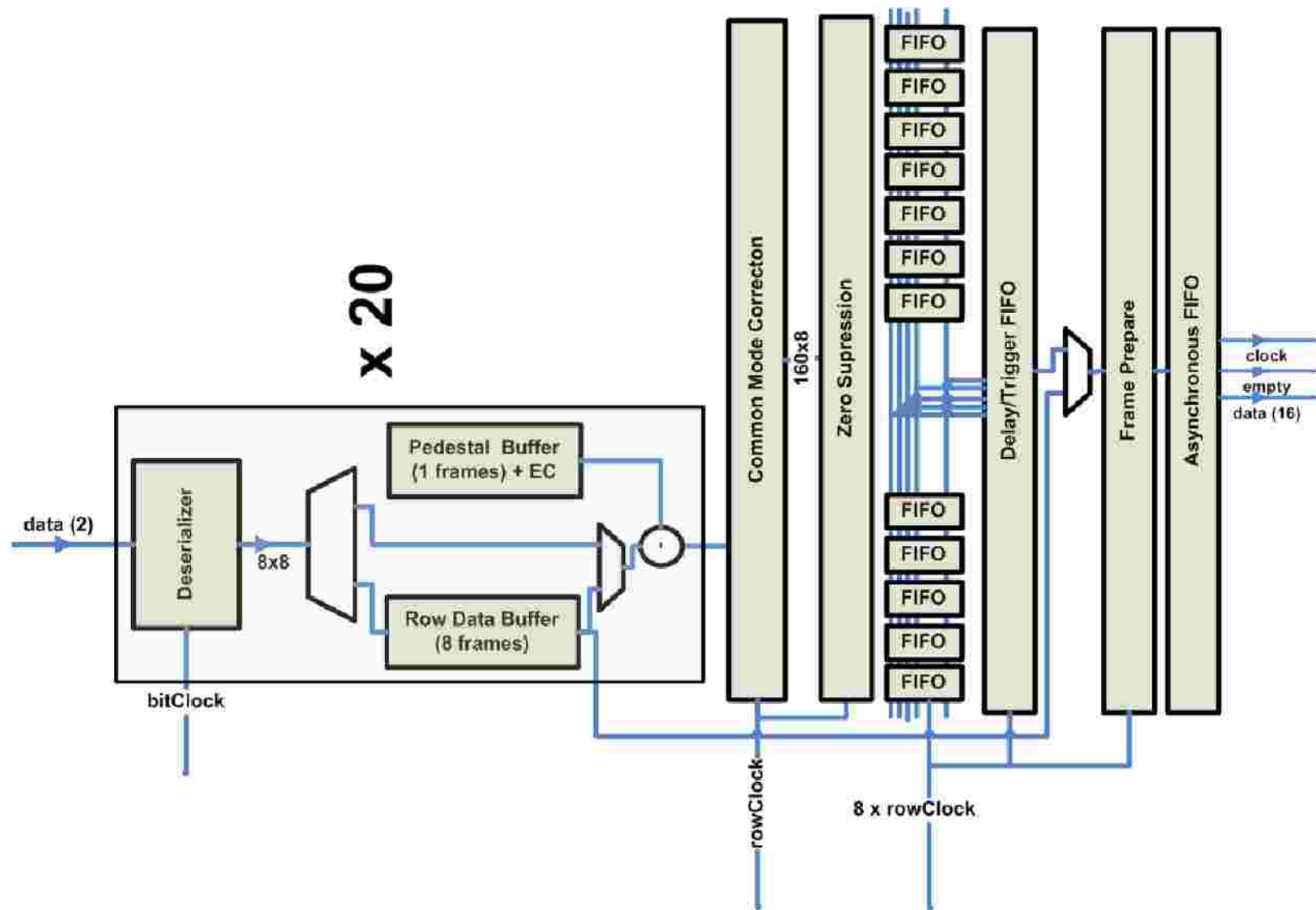
Data Handling Processor – DHP

- receive & de-serialize ADC data from the DCD
- raw data correction
 - pedestal subtraction → correct for fixed offset per individual pixel
 - common mode correction → time dependent offset for all simultaneously sampled pixels (quad-rows)
- data reduction
 - zero-suppression
 - trigger coincidence
- module control functionality
 - PLL
 - DCD / Switcher timing
 - slow control (JTAG)
- 90 nm tech.
- 6 chips per half module



University of Bonn & University of Barcelona

DHP Data Processing



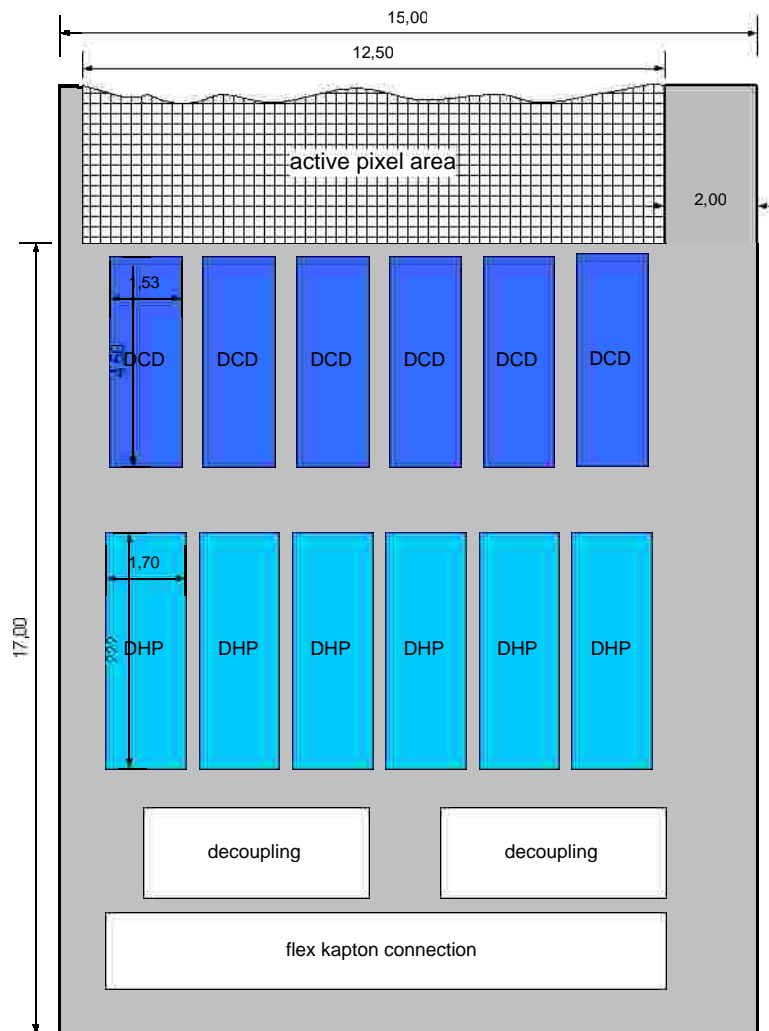
- DEPFET collaboration going to develop a pixel vertex detector for Belle 2
- Many design aspects make use of the ILC driven R&D
 - sensor development: thin sensor, 'all-silicon module'
 - chip development
- Prototypes of the Switcher chips designed and successfully tested, new development for higher output swing are under development
- DCD2 chip (test chip) close to final performance
- Design of the digital chip (DHP) just started

see talk by Carlos Lacasta on Friday afternoon for more details on the DEPFET sensor design & performance

Thank you!

backup

End of Module Layout



DCD

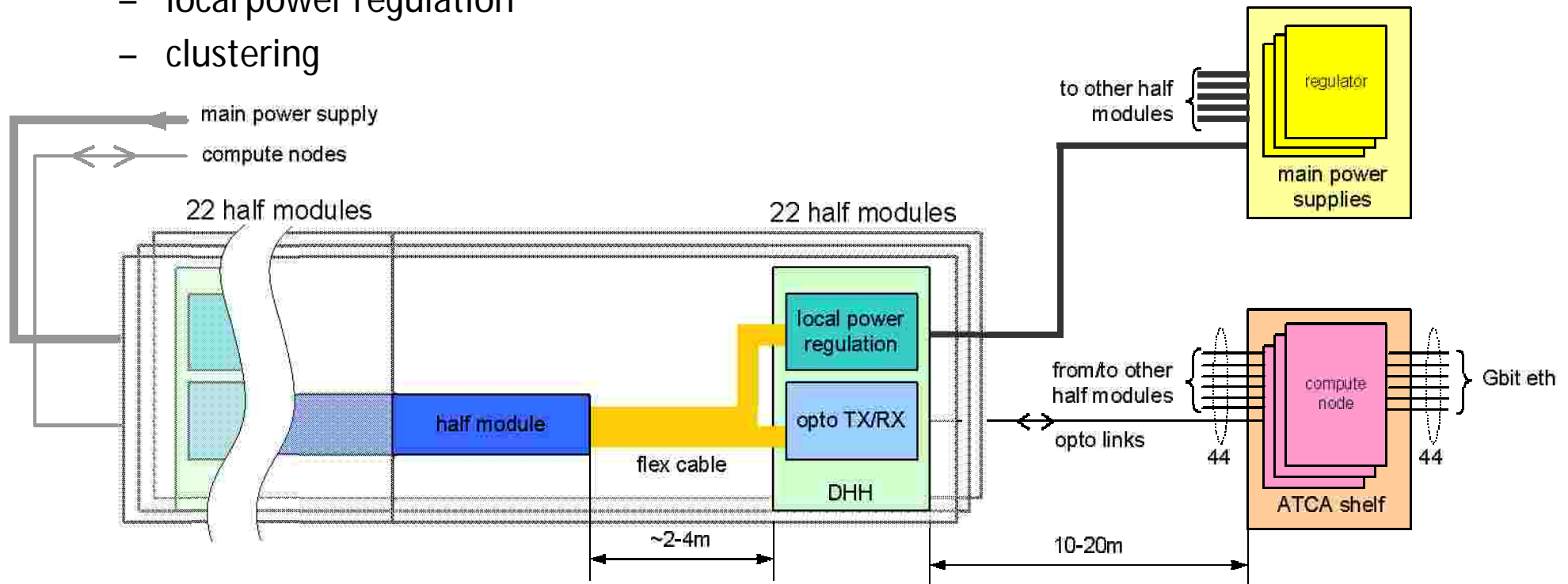
- 150 μm x 150 μm cells
- 6 chips, 1.5 x 4.7 mm
- Input: 16 rows, 10 columns
- Output: 4 rows, 10 columns

DHP

- 200 μm bump bond pitch
- 6 chips
- 1.7 x ??? mm
- One 1Gbit link per DHP
à 6 Gbit per module
- Need to change input layout:
 - 5 rows, 8 columns

DEPFET PXD – Backend Electronic

- individual r/o for 44 half-modules
- intermediate board (data handling hybrid, DHH) between module and rack electronic (ATCA shelf with 'compute node' cards)
 - opto links
 - local power regulation
 - clustering



Switcher 4 – Implementation

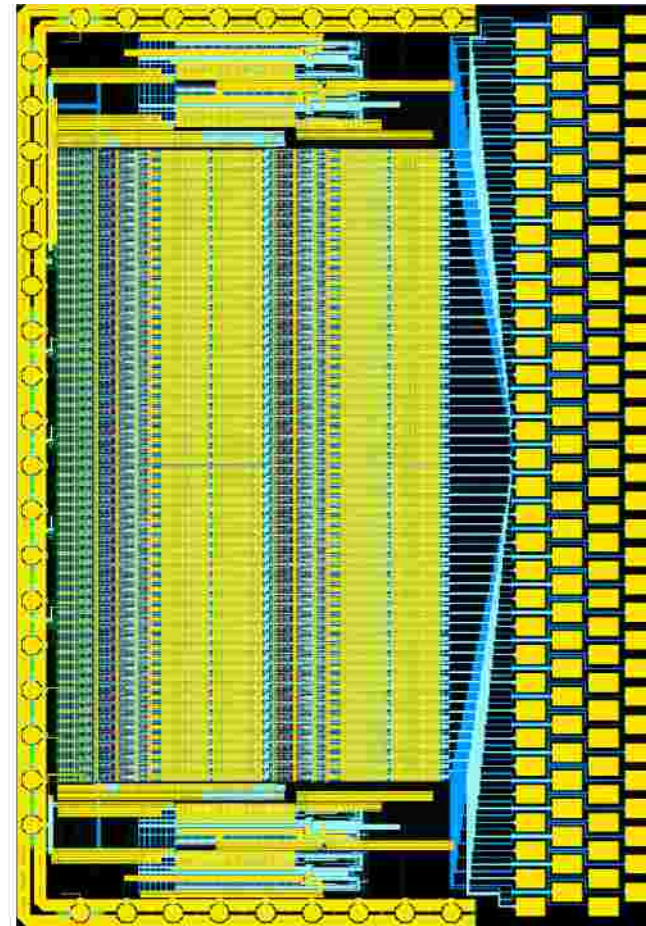
- 0.35 HV technology
- radiation tolerant
- 64 channels (x2, clear & gate)

pro:

- Possible operation up to 50 V (30V tested)
- gate and clear switches on one chip

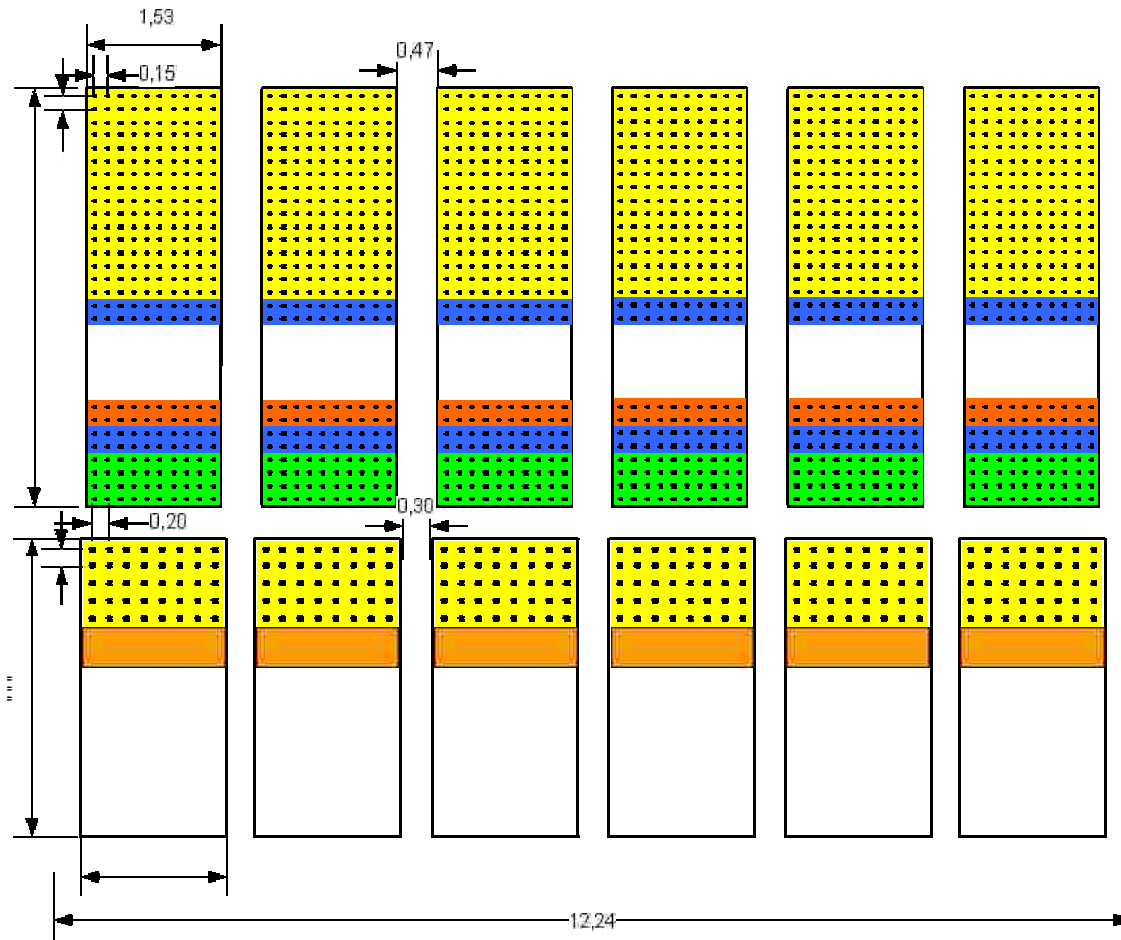
con

- not as fast as SW3
- moderate DC power consumption (0.4mW/channel)



University of Heidelberg

DCD + DHP footprints



6 chip DHP option

- Further reduced costs
- one Gbit link per chip @ 6 Gbit r/o per module
- but: even more redundant logic
- Need to change input pad layout
 - DCD: 4 x 10 @ 150 μ
 - DHP: 5 x 8 @ 200 μ



- SuperKEKB RF frequency $f_0 = 508$ MHz (508.89 MHz precisely)
- Number of slots per cycle: 5120
- Circulation time: 10.061 μ s
- System clock $f_0/12 = 42.3$ MHz (or $f_0/4$, $f_0/8$, $f_0/16$, $f_0/256$)
- Abort gap: 200 ns (~100 bunches)
- Clock for abort gap available (frame clock)

- DEPFET read-out synchronous with beam circulation (128 rows):
row clock = $508 \text{ MHz} / (5120/128) = 508 \text{ MHz} / 40 = 12.7 \text{ MHz}$
- Use $f_0/8$ and divide by 5 (DHH?)